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(54) RESIN COMPOSITION

(57)Abstract:

PURPOSE: To obtain a resin composition having excellent crack resistance in soldering and moisture resistance by blending mainly a modified reactional product obtained by reacting a specified polymaleimide with a silane coupling agent.

CONSTITUTION: This resin composition is manufactured by modifying (A) a polymaleimide containing ≥2 maleimide groups in one molecule (e.g. N,N'- ethylenebismaleimide) by reacting 100 pts.wt. of (A) with 0.1-25 pts.wt. of (B) a silane coupling agent of the formula (Y is univalent organic acid containing amino group; R1 to R3 are H, phenyl, OR (R is H or 1-5C alkyl), etc.; at least one of R1 to R3 is OR) (e.g. 3-aminopropyltrimethoxysilane) and blending the modified product with an epoxy resin containing ≥2 epoxy groups in one molecule and a hardener. Optionally the component A is mixed with a phenol resin, in advance.

$$R_{i}$$
|
 $Y-S_{i}-R_{z}$
|
 R_{i}

JP,06-157754,A [CLAIMS]

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CLAIMS

[Claim(s)] [Claim 1]A polymaleimide compound and a general formula (1) which have two or more malefmide groups in one molecule [-izing 1]

[Chemical formula 1]

$$\begin{vmatrix} 1 & & & \\ Y-S & I-R_2 & & (1) \end{vmatrix}$$

An organic group of monovalence in which Y contains an amino group among a formula, Ry, Ry, and R₃ A hydrogen atom, a phenyl group, an alkyl group of the carbon numbers 1-6. Or a thermosetting resin

composition which contains as a subject a reaction-of-degeneration thing to which are OR group (R shows an alky| group of a hydrogen atom or the carbon numbers 1–5.), and at least one of R_1 , R_2 , and the R_3

comes to carry out the reaction of degeneration of the silane coupling agent expressed with] which is -OR

Claim 2]The thermosetting resin composition according to claim 1 which made a polymaleimide compound contain phenol resin beforehand.

Claim 3]A resin composite by which an epoxy resin which has at least two epoxy groups being included in the thermosetting resin composition according to claim 1 or 2 and one molecule.

Claim 4]A resin composite for semiconductor closure which contains the resin composite according to

claim 1, 2, or 3 as a subject. [Claim 5]A resin composite for semiconductor closure which contains a resin composite according to claim l, 2, or 3 and an inorganic bulking agent as a subject.

[Translation done.]

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JP,06-157754,A [DETAILED DESCRIPTION]

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DETAILED DESCRIPTION

Detailed Description of the Invention

semiconductor device of which solder heat resistance is required like a surface mount type semiconductor Industrial Application]This invention is concerned with the resin composite excellent in heat resistance and moisture resistance. In particular, it is related with a resin composite suitable for closing the

tendency of multi-functionalization. The material which closes this is strongly expected development of the wiring board. As the resin composite to such a use, and what is called a resin composite for semiconductor [Description of the Prior Art]in recent years, the heat-resistant, crack resistant, and damp-proof outstanding resin composite is called for in the field of an electric electronic component, a semiconductor, wiring board which attaches parts with the miniaturization of an electric electronic component, apparatus, and equipment and slimming down which use this to become high, and the parts itself are especially in the composite which uses phenol novolak resin and silica as the main ingredients as that hardening agent are resin composite excellent in heat resistance to the high temperature solder in the soldering process to a closure, conventionally, The epoxy resin represented by o-cresol novolak type epoxy resin and the resin excellent in respect of a moldability and reliability, and serves as the mainstream in this field. "Kakiuchi etc. For example, in the field of a semiconductor, it is in the tendency for the packaging density to the *****; the epoxy resin P80, Shokodo Co., Ltd."

consists of epoxy resins, if the fall of the intensity at soldering temperature is intense, and it solders while mount type semiconductor device, the whole semiconductor device is put to the soldering temperature of Problem to be solved by the invention]However, speaking of a plastic molded type semiconductor device, it has been in the state in which the resin closed especially absorbed moisture since the glass transition water cannot be finished, a crack occurs in sealing resin, and the reliability of a semiconductor device is temperature is lower than soldering temperature, Resisting the stress by rapid expansion of hygroscopic it is changing to a surface mount type semiconductor device by the flow of the above-mentioned highdensity-assembly-izing. Unlike the conventional inserting type semiconductor device, in such a surface not less than 200 ** by the soldering process to a substrate. By the way, the resin composite whichreduced substantially.

time of an elevated temperature could be made high by application of imide resin and the crack resistance semiconductor device, exfoliation occurred in the interface of an element surface and resin by the thermal semiconductor device with which a reflow and flow soldering are made for closure by improving the solder persons made glass transition temperature of sealing resin high, are the purposes of giving sufficient resin strength which overcomes the stress generated by expansion of moisture, and came in piles the research which applies imide system resin to the resin composite for closure. As a result, although intensity at the shock at the time of soldering, and there was a problem that subsequent moisture resistance fell. The herefore, a passage given in JP,H1-213335,A, JP,H2-254735,A, and JP,H2-32117,A, This invention at the time of soldering improved, Imide system resin was inferior to the adhesive property with a purpose of this invention is to provide the resin composite applicable to the surface mount type proof crack nature at the time of mounting, and the moisture resistance after mounting. magazine; the Nikkei electronics June 13, 1988 item 114 - 118-page"

Means for solving problem]In order to solve an aforementioned problem, as a result of repeating research

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wholeheartedly, by denaturing a polymaleimide compound by the silane coupling agent which has an amino group, this invention persons find out that the adhesive property of the semiconductor device surface and resin improves, and came to complete this invention. That is, this inventions are (1) polymaleimide compound and a general formula (1). [-izing 2]

Chemical formula 2]

Y-S1-R2

 $\widehat{\Xi}$

reaction of degeneration of the silane coupling agent expressed. (2) The thermosetting resin composition of the organic group of the monovalence in which Y contains an amino group among a formula, $R_1,\ R_2,$ and R_3 resin composite for semiconductor closure which contains the resin composite and inorganic bulking agent bulking agent which make a subject the reaction-of-degeneration thing to which it comes to carry out the shows the alkyl group of a hydrogen atom or the carbon numbers 1-5.), at least one [and] of R₁, R₂, and — a hydrogen atom, a phenyl group, and the alkyl group of the carbon numbers 1-6. Or it is OR group (R the R_3 -OR group -- it is -- the resin composite consisting of the thermosetting resin and the inorganic of a description as a subject in the resin composite for semiconductor closure which contains the resin included in a thermosetting resin composition the above (1) or given in (2), and one molecule, (4) It is a beforehand, (3) A resin composite by which the epoxy resin which has at least two epoxy groups being composite of a description as a subject in the above (1), (2), or (3) and (5) above (1), (2), or (3). As a the above-mentioned (1) description which made the polymaleimide compound contain phenol resin polymaleimide compound used by this invention, it is a general formula (a). [-izing 3]

[Chemical formula 3]

3

A bis[4 - (3-maleimide phenoxy) phenyl] sulfoxide, A bis[4 - (4-maleimide phenoxy) phenyl] sulfoxide, A bis screw (4-maleimide phenyl) Methane, Screw (3-methyl-4- maleimide phenyl) Methane, screw (4-maleimide phenylene) Bismaleimide, N,N'-[1,3-] (2-methylphenylene) bismaleimide, N,N'-(1,4-phenylene) bismaleimide carbon atoms, and k shows two or more positive integers among a formula), and it is altogether usable if it compound, it is N,N', for example. – Ethylenebis maleimide, N,N'- Hexamethylene bismaleimide, N,N' – (1,3– ketone, A bis[4 - (3-maleimide phenoxy) phenyl] sulfide, Bis[4 - (4-maleimide phenoxy) phenyl] SURUIDO, [4 - (3-maleimide phenoxy) phenyl] sulfone, A bis[4 - (4-maleimide phenoxy) phenyl] sulfone, Bis[4 - (3-maleimide phenoxy)]phenoxy) Biphenyl, bis[4 - (3-maleimide phenoxy) phenyl] ketone, bis[4 - (4-maleimide phenoxy) phenyl] It is a polymaleimide compound expressed with ($R_{
m A}$ is an organic group of k value which has at least two screw (4-maleimide phenoxy) Benzene, 1,3-screw (3-maleimide phenoxy) Benzene, bis[4 - (3-maleimide maleimide phenoxy) phenyi] ether, Bis[4 - (4-maleimide phenoxy) phenyi] ether, 1,4-bis[4-(4-maleimide phenoxy) phenyl] butane, 2,2-bis[4 - (4-maleimide phenoxy) phenyl] butane, 2,2-screw [4-(3-maleimide phenoxy) phenyl] propane, 2,2-bis[4-(4-maleimide phenoxy) phenyl] propane, 2,2-bis[4 - (3-maleimide Cyclohexane, 1,4–screw (maleimide methyl) Cyclohexane, 1,4–screw (maleimide methyl) Benzene, 1,3– phenoxy) phenyl] ethane, 1,2-bis[4 - (4-malcimide phenoxy) phenyl] ethane, 2,2-bis[4 - (3-maleimide phenoxy) pheny] ethane, 1,1-bis [4 - (4-maleimide phenoxy) pheny] ethane, 1,2-bis [4 - (3-maleimide 1,1,1,3,3,3-hexafluoropropane, 4,4'-sorew (3-maleimide phenoxy) Biphenyl, 4,4' - Sorew (4-maleimide phenoxy) pheny]] methane, bis[4 - (4-maleimide phenoxy) pheny]] methane, 1,1-bis[4 - (3-maleimide phenyl) Ether, Screw (4-maleimide phenyl) A sulfone, screw (4-maleimide phenyl) Sulfide, Screw (4maleimide phenyl) ketone, sorew (4-maleimide cyclohexyl) Methane, 1,4-screw (4-maleimide phenyl) phenoxy) phenyl]-1,1,1,3,3,3-hexafluoropropane, 2,2-screw [phenyl [4 - (4-maleimide phenoxy)]]is a compound which has two or more maleimide groups in one molecule. As such a polymaleimide

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alpha and alpha – dimethylbenzyl] benzene, 1,4-bis[4-(3-maleimide phenoxy)-3,5-dimethyl- alpha and alpha dimethylbenzyl] benzene, 1,4-bis[4-(3-maleimide phenoxy)-alpha and alpha - dimethylbenzyl] benzene, 1,3bis[4-(3-maleimide phenoxy)-alpha and alpha – dimethylbenzyl] benzene, 1,4-bis[4-(4-maleimide phenoxy)-3,5-dimethyl- alpha and alpha – dimethylbenzyl] benzene, 1,3-bis[4-(4-maleimide phenoxy)-3,5-dimethylphenoxy)-alpha and alpha – dimethylbenzy]] benzene, 1,3-bis[4-(4-maleimide phenoxy)-alpha and alpha – dimethylbenzy[] benzene, 1,3-bis[4-(3-maleimide phenoxy)-3,5-dimethyl- alpha and alpha -dimethylbenzyl] benzene, a general formula (2) [-izing 4]

Chemical formula 4

3

The polymaleimide compound expressed with (the inside of a formula and n are 0-10 by average value), and a general formula (3) [-izing 5] 8000

Chemical formula 5]

3

average value) are mentioned. These polymalcimide compounds may be used independently, or two or more kinds may be mixed and they may be used. The silane coupling agent used for this invention is expressed The polymaleimide compound etc. which are expressed with (the inside of a formula and m are 0-10 by with the above-mentioned general formula (1).

propylsilane, 3-dibutylamino propyltrimethoxysilane etc. are raised, and these things are independent or are copies of silane coupling agents and restriction in particular does not have the mixing ratio of phenol resin polymaleimide compounds, those total quantities are preferred and about 1 to 50 weight % is practical. The propyltrimethoxysilane, 3-cyclohexylamino propyltrimethoxysilane, N-(3-triethoxy silyl propyl) urea, N-(3aminopropyl) trimethoxysilane, $3-(2-aminoethyl\ aminopropyl)\ dimethoxymethylsilane,\ <math>3-[2-(2-aminoethyl)]$ mixture ratio of a polymaleimide compound and a silane coupling agent, although it is the range of 0.1–25 than a part, and if it exceeds 25 copies, a silane coupling agent independent reaction will start and it will loadings of a silane coupling agent are 0.1. A reaction of degeneration is insufficient for the case of less thioethyl) diethoxymethylsilane, 3-piperazino propyltrimethoxysilane, a dimethoxymethyl 3-piperazino polymaleimide compound, phenol resin and a silane coupling agent, and is performed. In this case, the briethoxy silyl propyl}−p−nitrobenzamide, 2–(2−aminoethyl thioethyl) triethoxysilane, 2–(2−aminoethyl coupling agent carries out heating mixing of a polymaleimide compound, a silane coupling agent, or a used by two or more sorts. The reaction of degeneration of a polymaleimide compound and a silane aminoethyl amino) propyl] trimethoxysilane, 3-phenylamino propyltrimethoxysilane, 3-benzylamino (0009]As an example of this silane coupling agent, 3-aminopropyl trimethoxysilane, 3-aminopropyl to a polymale mide compound to 100 copies (a weight section and the following -- the same) of aminopropyldimethylmethoxysilane, 2-aminoethyl aminomethyl trimethoxysilane, 3-(2-aminoethyl triethoxysilane, 3-aminopropyl dimethoxymethylsilane, 3-aminopropyl diethoxymethylsilane, 3have an adverse effect on moisture resistance.

independent [of the thing which is excellent in heat resistance], a moldability and heat resistance can be nolecule as this epoxy resin. About these, it illustrates below. Phenols and formaldehyde, such as phenol, palanced by using together with other resin. Concomitant use with an epoxy resin is preferred especially from this viewpoint, and it is altogether usable if it is a thing which has at least two epoxy groups in one [0010]Since imide resin has a problem in respect of flexibility and a moldability when it is used by

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JP,06-157754,A [DETAILED DESCRIPTION]

epoxy resin derived from novolak resin which is a resultant of aldehyde, such as guru oxal and alkanedial And the aralkyl type epoxy resin derived from aralkyl resin which is a resultant of the above-mentioned cresol, resorcinol, and naphthol, Acetaldehyde, benzaldehyde, hydroxybenzaldehyde, The novolak type phenols and an aralkyl alcohol derivative is preferred from a point of heat resistance and an electrical

is 25–300 weight section preferably, moreover — the rate of an epoxy resin and a hardening agent receives of oil, and the shape of rubber, denaturalizing. For example, Provisional Publication No. No. 270617 [62 to] a weight section, the total quantity of an epoxy resin and a hardening agent --- 10-500 weight section --- it and bis(4-aminophenyl)methane; Adipic acid, The epoxy resin etc. which are produced by making polyvalent hydroxybenzaldehyde, Novolak resin which is a resultant of aldehyde, such as guru oxal and alkanedial, And together in the reaction—of—degeneration thing to which it comes to carry out the reaction of degeneration formula (1) in the constituent of this invention, it is the reaction-of-degeneration thing 100. As opposed to groups in one molecule, For example, bisphenol A, the bisphenol F, resorcinol, screw hydroxydiphenyl ether, polymer. Although publicly known things, such as phenols, amines, and an acid anhydride, can be used as a the epoxy group of an epoxy resin — a hardening agent — equivalent ratio — the range of 0.1-10 — it is 0012]It can also be used for the aforementioned epoxy resin with silicone compounds, such as the shape phenol; Ethylene glycol, Neopentyl glycol, glycerin, trimethylolpropane, pentaerythritol, Polyhydric alcohol of the silane coupling agent expressed with a polymaleimide compound and the above–mentioned general classes, such as a diethylene glycol and a polypropylene glycol; Ethylenediamine, Amines, such as aniline 4,4'- screw hydroxy-3,3',5,5'- Tetramethyl biphenyl, Tetra bromine bisphenol A, dihydroxynaphthalene, a manufactured by distributing the particles of silicone polymer in the reactant of an epoxy resin and vinyl carboxylic acid, such as phthalic acid and isophthalic acid, epichlorohydrin, or 2∸methyl epichlorohydrin derivative, such as aralkyl resin, a trihydroxy phenylmethane, tetra hydroxyphenyl ethane, and tetrakis the polyhydric phenol which are the resultants of the above-mentioned phenols and an aralkyl alcohol . [0011]In addition, the epoxy resin derived from the compound which has two or more active hydrogen trihydroxy phenylmethane, Polyhydric phenol, such as tetra hydroxyphenyl ethane and alkane tetrakis nardening agent of said epoxy resin, phenol resin is used most preferably. For example, phenols and phenol, is mentioned, and these one kind or two kinds or more are used. When using an epoxy resin Provisional Publication No. As indicated by No. 273222 [62 to], it is silicone modified epoxy resin formaldehyde, such as phenol, cresol, resorcinol, and naphthol, Acetaldehyde, benzaldehyde, react are mentioned, and one kind of these epoxy resins or two kinds or more are used. the range of 0.5-2.0 preferably.

coupling agent is preferred also in it, and the Silang system coupling agent which has a reactant functional powder of the crystallinity from a point of a coefficient of thermal expansion and thermal conductivity and granular material; glass fibers, such as crystalline silica, fused silica, alumina, silicon nitride, silicon carbide, melting nature is preferred. The mixture of the silica powder of the fluid point at the time of shaping to a section, and the loadings of an inorganic bulking agent are 200-600 preferably. It is a weight section. The above-mentioned inorganic bulking agent may reform the surface beforehand by finishing agents, such as globular form or a globular form, and an infinite form is preferred. To the thermosetting resin 100 weight the Silang system, a titanate system, an aluminate system, and a zircoaluminate system coupling agent, tale, silicic acid calcium, calcium carbonate, mica, clay, and a titanium white, and carbon fiber, The silica section which makes a reaction-of-degeneration thing a subject, it is required to be 100 -900 weight inorganic granular material or a fibrous body is usable, for example, there are fibrous bodies, such as apart from the silane coupling agent used for this invention as occasion demands. The Silang system [0013] The inorganic bulking agent used in the constituent of this invention, Although the thing of an group especially is the most preferred.

głycidoxypropylmethyldimetoxysilane, 2-(3,4-epoxycyclohexyl) ethyltrimethoxysilane, 3-methacryloxy propyl :0014]As an example of this Silang system coupling agent, Vinytrimetoxysilane, vinyltriethoxysilane, N-(2aminoethyl)3-aminopropyl methyl dimethoxysilane, N-(2-aminoethyl)3-aminopropyl trimethoxysilane, 3trinethoxysilane, 3-mercapto propyltrimethoxysilane, etc. can be mentioned, and these one kind or two aminopropyl triethoxysilane, 3-anilino propyłtrimethoxysilane, 3-glycidoxypropyltrimetoxysilane, 3kinds or more are used

phosphine; Tetraphenyl phosphonium tetraphenylborate, Tetraphenylboron salts, such as triethyl ammonium ethylimidazole, and 2-heptadecylimidazole; Triethanolamine, Amines, such as a triethylene diamine and Ncontain and as this hardening accelerator, Imidazole derivatives, such as 2-methylimidazole, 2-methyl-4-[0015]In hardening a resin composite, in this invention, It is desirable to make a hardening accelerator methyl morpholine; Tributyl phosphine, Organio phosphine, such as triphenyl phosphine and tritolyl

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organic peroxide and an azo compound together if needed. The content of these hardening accelerators is hardening accelerators may be used independently, may use two or more kinds together, and can also use used in the range of 0.01 to 10 weight section to thermosetting resin 100 weight section which makes a tetraphenyl borate; the 1,8-diaza-bicyclo (5, 4, 0) undecene 7 and its derivative are mentioned. These reaction-of-degeneration thing a subject

compounds, such as fatty acid salt and a wax, antimony, and a phosphorus; colorant, such as carbon black, [0016]The resin composite of this invention if needed besides the various above-mentioned ingredients Diallyi phthalate, Reactive diluent; several-Kinds silicone oil generally used to imide resin, such as triallyl isocyanurate and o.o.' diarylbisphenol A; Fatty acid, Fire retardant, such as mold lubricant, bromine etc. can be blended, and it can mix and mull, and can be considered as a molding material.

Working example]Hereafter, an embodiment explains this invention concretely. In an embodiment, the test method of the performance of a constituent is as follows.

- glass-transition-temperature: -- TMA method and bending strength: -- JIS K-6911 and solder immersion constant temperature/humidity chamber for 168 hours, it is immersed in a 260 ** molten solder bath for 10 test: --- immediately after neglecting 25 semiconductor devices for an examination to 85 ** and 85% of

hen, the number of the semiconductor devices which the crack generated in package resin was counted.

The damp-proof test after solder immersion : In a solder immersion test, a crack the semiconductor device for an examination by which it was not generated - 121 **, It is neglected in a 2-atmosphere pressure cooker tester, electrical continuity is checked for every fixed time, and the poor incidence rate by the corrosion of aluminum wiring measures time to reach to 50%.

[0018] Example A-G of manufacture (manufacture of reaction-of-degeneration thing A-G)

and a condensator, it warmed at 160 **, the silane coupling agent was inserted so that it might become the The polymaleimide compound was inserted in the reaction vessel equipped with an agitator, a thermometer, presentation of A-G of the 1st table, and you made it react for 3 minutes, it cooled immediately, and

[0019]Example H–K of manufacture (manufacture of reaction=of-degeneration thing H–K) reaction-of-degeneration thing A-G was obtained.

A polymaleimide compound and phenol resin are inserted in the reaction vessel equipped with an agitator, a thermometer, and a condensator, and it warms at 160 **, and is the 1st table. The silane coupling agent was inserted so that it might become the presentation of H-K of [Table 1], and you made it react for 5 minutes, it cooled immediately, and reaction-of-degeneration thing A-G was obtained.

Table 1]

JP,06-157754,A [DETAILED DESCRIPTION]

第1表

ノボラック型 フェノール機器 (重量部)								7.08	20.7	20.7	20.7
シランカップ リング類 (重量部)	KBM603	KBM602	SZ-6083	A-187	KBM603	SZ-6083	A-187 5	KBM603	SZ-6083	KBM6 0 3	SZ-6083
表リケレイミド 化合物 (管量部)	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(2) 100	ポリマレイミド 化合物(2) 100	ポリマレイミド 化合物(2) 100	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(1) 100	ポリマレイミド 化合物(2) 100	ポリコレイミド 化合物(2) 100
性反応物	¥	В	ט	Q	а	F	Ü	Ħ	_	ſ	K

ground, was tableted and the molding resin composition was obtained. The following were used for the raw presentation (weight section) shown in [Table 2] was mixed with the Henschel mixer, and melting and the mull of were done for 3 minutes with a further 100–130 ** hot calender roll. This mixture was cooled and 0021]Embodiments 1-9 and the comparative example 1 - the 8 2nd table The compound of the material used all over the 1st and 2nd table.

 Polymaleimide compound (1); bis(4-maleimide phenyl)methane (product made from Mitsui Toatsu Chemicals Chemistry)

 Polymalcimide compound (2),4,4'-bis(3-malcimide phenoxy)BIFU ENIRU (made by Mitsui Toatsu Chemicals, Inc.)

 Bromine-ized epoxy resin, bromine-ized phenol novolak type epoxy resin (BREN -S, Nippon Kayaku Co., Epoxy resin; o-cresol novolak type epoxy resin (EOCN-1020, Nippon Kayaku Co., Ltd. make)

td. make)

- Inorganic bulking agent (1); globular form fused silica with a mean particle diameter of 20 micro (Hari Mick - Hardening agent; novolae type phenol resin (PN-80, Nippon Kayaku Co., Ltd. make) S-CO, Micron Make)

- Inorganic bulking agent (2); infinite form fused silica with a mean particle diameter of 13 micro (made in fuse REXX RD-8 Tatsumori)

- Silane coupling agent; 3-(2-aminoethyl aminopropyl) trimethoxysilane (KBM603, Shin-Etsu Chemical Co., Ltd. make

 Silane coupling agent; 3-(2-aminoethyl aminopropyl) methyl dimethoxysilane (KBM602, Shin-Etsu Chemical Co., Ltd. make) http://www4.ipdl.inpit.go.jp/ogi-bin/tran_web_ogi_ejje?atw_u=http%3A%2F%2Fwww4.ipdl.inpit.go... 2010/10/19

Silane coupling agent: 3-phenylamino propyltrimethoxysilane (SZ-6083, Dow Corning Toray Silicone

Silane ooupling agent; 3-glycidoxypropyltrimetoxysilane (A-187, Nippon Unicar make)
 A fire-resistant auxiliary agent (antimony oxide; made by Sumitomo Metal Mining Co., Ltd.)

- Hardening accelerator (C₁₇Z; made in Shikoku Chemicals)

[0022] [Table 2]

(55504 11	0.0	010					¹				I		1				
9015th fatight	0.8 0.8	5.0 0.3	0.4	6.0	5.0 5.0	0.3	5.0 E.D	9°9	5.0 0.3	5.0 5.0	0.3	0°3	6.0	5.0 6.0	5.0 0.3	0.4	P.0 E.0
749-K	0.2 0.2	S.0 S.0	S.0 S.0	2.0 2.0	2.0 2.0	2.0 S.0	S.0 S.0	\$.0 \$.0	0.2	1002	S.0 S.0	S.0 S.0	2.0	2.0 5.0	2.0 5.0	2.0 2.0	2.0 S.0
会化が発	Q.I	ō°ī	0.1	0.1	9.1	Ŏ-Ĭ	ĎŤ	ō•i	Ĩ'O	ĩ Ó	ŏ-ĭ	Ŏ-Ĭ	0-1	ŏ•ĭ	D'I	i.o	0-Ĭ
2209725 209HED					,				<u> </u>			67.0	2T,Q	2T.0			
00-24-344 8-09 x4-4k-23	0.23) 30.08	45.0 30.0	0.0£	9.05	30°0 12°0	0,5≱ 30,0	0.21. 0.05	85	0.53 30.0	8 9 9	85 85	15.0	0.63 30.0	0.25 0.08	0.25. 0.25.	45.0 30.0	0.0£
PK-80	I E	1.8	1.8	1.8	3"1					1.8	3.1	3°1	1.6	1.8	3.1	1.6	6.8
8-22-1030 S-22-1030	J'0 2°9	6.5 0.1	6.3 6.1	6.2 0.1	6.8 1.0	6,9 1,0	6.5 0.1	0°1 6°9	0'T 6'S	0°T 6'9	6.3 0.1	5.9 1.0	J*0 2*8	6*9 6*9	6.5 0.1	6.8 0.1	1.61 1.0
A 地位区域 图 地位区域 2 电线区区域 2 全域区域 2 全域区区域 2 全域区区域 3 有线区区域 4 电线区区域 4 电线区区域 5 电线区区域 5 电线区区域 5 电线区区域 6 电线区区域 6 电线区区域 6 电线区区域 7 电线区区域 6 电线区域 6 电线 6 电 6 电 6 电 6 电 6 电 6 电 6 电 6 电	7 2°0	72°0	T2*0	0.81	0:ST	T-8T	1.81	t*8 T	1.81	0.21	TE'D	o-gr	1P°0	o.st	7 2° 0	reo	
	τ	3	3	+	S	9	L	8	6	ī	3	E	,	S	9	L	8
			×		朝		M				Ħ	7	3	3	4		

Hardening accelerator (TPP-K; made by Hokko Chemical Industry Co., Ltd.)

Mold lubricant (Hoechst wax OP; made by Hoechst Japan)

- Colorant (carbon black; product made from Mitsubishi Kasei Industry)

http://www4.ipdl.inpit.go.jp/cgi-bin/tran_web_cgi_ejje?atw_u=http%3A%2F%2Fwww4.ipdl.inpit.go.. 2010/10/19 element mounting part of the leadframe for flat package type semiconductor devices. . Connect these with examination (10 mmx10 mm square) which gave 10-micro-wide aluminum wiring, the semiconductor device After connecting a leadframe and a bonding pad part by the gold streak which carries the element for an measurement was fabricated using the molding resin composition produced by making it above. To the four corners with 100micro x 100 micro, and the 1-micro-thick bonding pad part made from aluminum. By transfer molding (for 180 **, 30kg/om², and 3 minutes), the specimen for physical-properties

JP,06-157754,A [DETAILED DESCRIPTION]

for an examination was obtained by transfer molding (for 180 ** and 30-kg/cm² and 3 minutes). These molded products for an examination performed postcure at 180 ** for 6 hours, before doing each examination. It is the 3rd table about a test result. It is shown in [Table 3].

(Table 3] [0023]

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09T	210	022	210	512	513	SIO	ozz	510	510	SIZ	818	SIO	OIZ	920	082	062	東部名詞なそれ (ブ)
13.0	0.11	14.0	0'71	377	14.5	2.21	13.5	0.51	14.0	E-MI	14.3	14.0	0 '7 T	14.5	14.5	2.M	医左右 激发节度 (5m/3d)
0.1	0.8	3. 3	6.0	5.3	5.3	6' }	1'9	9.6	0.8	£.2	5.3	0.8	0. č	č. č	9*9	5.5	(#\$/##J) 華兵孫孫 360 C
9*1	1.8	£.1) *1	1.1	3 -1	£.1	1.3	£.1	£.1	rτ	1.3	8°1	£.1	1.3	1.3	1.3	(3./s-0(×) 本版和 第
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[Effect of the Invention] As the embodiment and the comparative example explained, the resin composite by subsequent moisture resistance. Therefore, when the surface mount type semiconductor device with which a reflow and a flow soldering method are applied is closed with this resin composite, the outstanding this invention is a resin composite excellent in the crack resistance at the time of mounting, and solder-proof crack nature and moisture resistance can be shown, a reliable plastic molded type semiconductor device can be obtained, and it is useful invention industrially

[Translation done.]

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